1. Record Nr. UNINA9910437802903321

Autore	Hofmann S (Siegfried)
Titolo	Auger- and x-ray photoelectron spectroscopy in materials science : a user-oriented guide / / Siegfried Hofmann
Pubbl/distr/stampa	Berlin ; ; Heidelberg, : Springer, 2012
ISBN	3-642-27381-5
Edizione	[1st ed. 2013.]
Descrizione fisica	1 online resource (543 p.)
Collana	Springer series in surface sciences ; ; 49
Disciplina	543.62
Soggetti	X-ray photoelectron spectroscopy Auger effect
Lingua di pubblicazione	Inglese
Formato	Materiale a stampa
Livello bibliografico	Monografia
Note generali	Description based upon print version of record.
Nota di bibliografia	Includes bibliographical references and index.
Nota di contenuto	Outline of the Technique/Brief Description -- Theoretical Background -- Instrumentation -- Practical Surface Analysis with AES -- Data Evaluation/Quantification -- Problem Solving with AES (Examples).
Sommario/riassunto	To anyone who is interested in surface chemical analysis of materials on the nanometer scale, this book is prepared to give appropriate information. Based on typical application examples in materials science, a concise approach to all aspects of quantitative analysis of surfaces and thin films with AES and XPS is provided. Starting from basic principles which are step by step developed into practically useful equations, extensive guidance is given to graduate students as well as to experienced researchers. Key chapters are those on quantitative surface analysis and on quantitative depth profiling, including recent developments in topics such as surface excitation parameter and backscattering correction factor. Basic relations are derived for emission and excitation angle dependencies in the analysis of bulk material and of fractional nano-layer structures, and for both smooth and rough surfaces. It is shown how to optimize the analytical strategy, signal-to-noise ratio, certainty and detection limit. Worked examples for quantification of alloys and of layer structures in practical cases (e. g. contamination, evaporation, segregation and oxidation) are used to critically review different approaches to quantification with respect to average matrix correction factors and matrix relative sensitivity factors. State-of-the-art issues in quantitative, destructive and non-destructive

depth profiling are discussed with emphasis on sputter depth profiling and on angle resolved XPS and AES. Taking into account preferential sputtering and electron backscattering corrections, an introduction to the mixing-roughness-information depth (MRI) model and its extensions is presented. .

2. Record Nr. UNIORUON00311150

Autore	SOUSA HOLSTEIN, Mariana : de, condessa de Alva
Titolo	Um olhar feminino sobre Portugal : Mariana de Sousa Holstein, condessa de Alva : cartas a sua irma Teresa, 1814-1819 / ediçao, estudo introdutório e notas António Ventura
Pubbl/distr/stampa	Lisboa, : Livros Horizonte, c2006
ISBN	97-224-1454-2
Descrizione fisica	405 p., [8] c. di tav. : ill. ; 24 cm.
Disciplina	946.903 4
Soggetti	Donna - Portogallo - Lettere e carteggi NOBILTA' - Portogallo - Lettere e carteggi PORTOGALLO - Biografie
Lingua di pubblicazione	Portoghese
Formato	Materiale a stampa
Livello bibliografico	Monografia